

Amendments to the Specification:

At page 19, kindly delete the Abstract and replace this with the present abstract beginning at line 2.

A plasma detector is provided inside an upper electrode of a parallel plate type dry-etching apparatus. Upon reaching a particular pressure at the detector, the etching apparatus is deactivated. This deactivation may be used to replace an ineffective gas introducing plate. The plasma detector measures a pressure of the plasma at the backside of the gas-introducing plate, which has gas holes therein. As the gas holes increase during use of the apparatus, the pressure of the plasma at the backside of the gas increases, and the function of the apparatus is compromised. By detecting the pressure of the plasma, defective conditions in the apparatus may be detected.